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Photophysical properties of SrTaO$_2$N thin films and influence of the anion ordering: a joint theoretical and experimental investigation

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ABSTRACT: Converting photon energy to chemical energy using inorganic materials requires successful capturing of photons, excitons dissociation and charge carriers diffusions. The present study reports thorough analysis of optoelectronic properties of visible-light-responsive SrTaO$_2$N perovskites to quantify its absorption coefficient, the generated charge carriers’ effective masses, dielectric constants, and electronic structures. The measurements on such intrinsic properties were attempted using both epitaxial and polycrystalline SrTaO$_2$N films deposited by radio frequency (RF) magnetron sputtering under N$_2$ reactive plasma. Density functional theory calculations using the HSE06 functional provided reliable values of these optoelectronic properties. Such quantities obtained both by the measurements and the calculations gave excellent correspondences, but also provide possible variations that account for the small discrepancies observed. One of the significant factors determining the optical properties was found to be the anion ordering in the perovskite structure imposed by the cations. As a result, the different anion ordering has noticeable influence in the optical properties and the large sensitivity of hole effective mass. Determination of relative band positions to the water redox properties was also attempted by Mott-Schottky plots. All these results offer the opportunity to understand why SrTaO$_2$N material possesses intrinsically all the ingredients to lead to a highly efficient water splitting device.

1. Introduction

Solar photoconversion is one of the most important environmentally friendly ways to satisfy the world’s energy demand. On a physical level, solar photoconversion mechanism involves many steps, starting from photon absorption, electron-hole pair dissociation followed by charge carrier diffusion and ending with the electrochemical reactions happening of the surface of the catalyst. For this purpose, the synthesis of visible-light-responsive semiconducting materials has gained tremendous attention. Some perovskite oxynitride materials, such as LaTiO$_3$N, SrTaO$_2$N and BaTaO$_2$N, absorb substantial amounts of light in the visible-light range and are considered to be efficient photocatalytic materials in addition to being used as non-toxic inorganic pigments. These oxynitride compounds have the ABO$_3$N characteristic formula wherein A is often a lanthanide, an alkaline or an alkaline earth ion, and B is a transition metal ion. For a cubic lattice, the cation A with a large ionic radius occupies 12-coordinated sites at each vertex of the cube, the cation B with a smaller radius is located at the center of the cube coordinated by 6 anions, oxygens and nitrogens located at the face centers of the cube. This structure reveals the existence of an octahedral BO$_6$N$_3$ stacking structure in which each cation B is surrounded by four O and two N ions. Due to their crystal lattice flexibility, it is possible to

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produce different cationic and/or anionic substitutions, which result in the formation of new solid solutions associated with a progressive or abrupt change in the physical, chemical, optical or catalytic properties.\textsuperscript{9,20-27}

Most oxides and oxy nitride perovskites have semiconductor characteristics in which the top of the valence band (VB) is principally composed of the anion’s atomic orbitals, and the bottom of the conduction band (CB) is principally composed of the transition metal's atomic orbitals. The presence of nitrogen, being a less electronegative element than oxygen, will lead to a higher-lying valence band, decreasing the bandgap. Typically, these materials' parent oxides have bandgaps that are higher than the targeted solar energy range. The introduction of nitrogen can therefore increase these materials’ photocatalytic activity.\textsuperscript{9,10,26}

In this work, the structural, optical and charge carrier transport properties of SrTaO$_3$N$_2$, a key material for water splitting,\textsuperscript{9} were evaluated via experimental measurements and first principles computations. Herein, we employed epitaxial and polycrystalline SrTaO$_3$N$_2$ thin films to acquire more accurate measurements of the photophysical properties.\textsuperscript{9,40} SrTaO$_3$N$_2$ thin films were deposited by reactive radio frequency (RF) magnetron sputtering on 0.5 at% Nb-doped SrTiO$_3$ (Nb:STO) and MgO substrates. The photophysical properties of the SrTaO$_3$N$_2$ films were evaluated by UV-Visible spectroscopy and the structural characterization was obtained by X-ray diffraction analysis. Furthermore, all these experimental characterizations were supported by Density Functional Theory (DFT) calculations offering an atomistic interpretation of these quantities and probing the sensitivity of the photophysical properties to the anion ordering. Our particular protocol allows a deeper investigation of the fundamental properties of photoabsorbers in solar cells.

2. Experimental and Theoretical Approaches

2.1. Experimental. SrTaO$_3$N$_2$ thin films were deposited by RF magnetron sputtering using a reactive plasma gas mixture of Ar and N$_2$. The starting material used for sputtering was a home-made SrTaO$_3$ oxide powder. It was synthesized via a solid-state chemical route from stoichiometric amounts of SrCO$_3$ and Ta$_2$O$_5$ heated under air at 1400°C for 30 h. The sputtering target was a 2 mm thick and 3 inch wide disk formed by cold pressing SrTaO$_3$ oxide powder under 80 MPa. The target was sputtered with an input power of 2.05 W cm$^{-2}$ (90 W). The initial chamber pressure was pumped down to 10$^{-7}$ mbar. During deposition, the pressure was maintained at 40 mbar via the leak valve. Depositions were performed at substrate temperatures (T$_s$) ranging from 800 to 900°C, and the nitrogen content in plasma was set at 20 vol.%.\textsuperscript{41} Films were deposited on the following two types of single-crystal substrates: (001) transparent MgO and conductive 0.5 at% Nb:SiTiO$_3$ (Nb:STO). The latter was used as a substrate and bottom electrode in the metal-insulating-metal (MIM) structures for the dielectric and electrochemical characterizations. Thicknesses were controlled by the sputtering time of the deposition.

X-ray diffraction patterns were obtained using a Seifert 3003 PTS diffractometer (Cu K$_{α1}$ radiation). Conventional 0-2θ patterns were recorded at 0.01° intervals with a 0.2 s count time at each step. θ-scan measurements were also performed at a tilt angle $χ = 45^\circ$ corresponding to the pseudo-cubic (100) plane of the oxy nitride compound to evaluate the possible epitaxial growth of films. The chemical composition of samples was determined by semi-quantitative Energy Dispersive Spectrometry (EDS) in a FEI Nova NanoSEM operating at 10 kV.

UV-visible transmittance and reflectance spectra were acquired using a JASCO V-570 spectrophotometer with an integrating sphere in the wavelength range of 300–800 nm. For each sample, the absorption coefficient $α$ was calculated from the transmittance and reflectance contributions. The band gap of the material was calculated assuming a direct allowed transition\textsuperscript{35} and using the relation:

$$
(abv)^2 = hν - E_g
$$

where $hν$ is the photon energy. In the plot of $(abv)^2$ as a function of $hν$, extrapolation of the linear region of the plot at zero gives the value of the bandgap ($E_g$).\textsuperscript{44}

Low frequency dielectric properties were measured by an LCR meter (LCR-891 GWInstek) on the MIM structures. The conducting substrate (Nb:SrTiO$_3$) was used as the bottom electrode, whereas 200 nm sputtered silver served as the top electrode.

Electrochemical impedance spectroscopy was performed to estimate the flatband potential ($E_{fb}$) of the prepared SrTaO$_3$N$_2$ films. We used a conventional three-electrode single electrochemical cell. The electrochemical impedance spectroscopic investigations were performed in a 0.1 M Na$_2$SO$_4$ solution (pH 8.8). For measurements, we used a potentiostat system (VMP3) from BioLogic Science Instruments. To determine the potential window for the Mott-Schottky (MS) analysis, cyclic voltammetry experiments were conducted under bubbling argon (Ar) with various scan rates from 10–500 mV s$^{-1}$ between 0.1 to 1.3 V vs. RHE. Impedance spectra were recorded between 10 Hz to 100 kHz under Ar bubbling, and the amplitude of the superimposed sinusoidal potential signal was 5 mV for each of the 70 steps in the potential window starting from 1.3 to 0.1 V vs. RHE under dark conditions. The MS plots only depict the potential window in which the faradaic current remains negligible in accordance with the cyclic voltammetry (CV). The flat band potentials ($E_{fb}$) of the films were obtained by extrapolation to the X-axis of the MS (C$^{-1}$ against potential), and the majority charge carrier concentration ($N_d$) was obtained from the slope of the linear fit according to the following equation:\textsuperscript{57,60}

$$
\frac{1}{C^2} = \frac{2}{A^2\varepsilon_{ss}^0 N_d} \left( E - E_{fb} - \frac{kT}{e} \right)
$$

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where $C$ is the interfacial capacitance, and $E$ is the applied potential. Here, the constant $A$ is the electrode area, $\varepsilon$ is the dielectric constant of the semiconductor, $\varepsilon_0$ is the permittivity of free space, $T$ is the absolute temperature, $e$ is the electric charge and $k_B$ is the Boltzmann’s constant.

2.2. Computational details. Geometry optimizations and frequency calculations were performed in the framework of DFT with the global hybrid functional PBE0\textsuperscript{46} using the \textit{ab initio} CRYSTAL14 code\textsuperscript{47,48}. The Kohn-Sham equations were solved self-consistently by developing the one-electron wave function on a localized (Gaussian) basis sets, thus allowing the efficient use of hybrid functionals. For the Sr atom, the Hay and Wadt small core pseudopotential was used along with the \textit{3sG(d)} basis set for the (10) valence electrons.\textsuperscript{49} For Ta, a small core pseudopotential developed by Baranetz et al. was used along with the \textit{3sG(d)} basis set for the (13) valence electrons.\textsuperscript{50} For the O and N atoms, the all electron basis sets \textit{8-41G(d)} and \textit{7-31G(d)} were used\textsuperscript{51} for the geometry optimizations, respectively, and the triple zeta basis set developed by Peintinger et al. was used for the HSE06 single point calculations.\textsuperscript{52} Reciprocal space was sampled with a $3\times3\times3$ k-point mesh for both the geometry optimization and vibrational calculations and a $9\times9\times9$ k-point mesh for the HSE06 single point calculations. The convergence criterion for the SCF cycle was fixed at 10$^{-6}$ Ha per unit cell for the geometry optimization and frequencies calculations.

The calculation of frequencies was performed within the harmonic approximation to the lattice potential, and the infrared intensities were obtained through the Berry Phase method.\textsuperscript{53} Finally, the vibrational contribution to the dielectric constant ($\varepsilon_{\text{th}}$) was computed with PBE0 using the CRYSTAL14 code (DOI: 10.1002/qua.24658). All electronic properties were computed using the HSE06\textsuperscript{54} functional on the PBE0 geometries. For the electronic contribution to the dielectric constant (denoted $\varepsilon_e$), calculations were performed using the VASP code (version 5.3.3)\textsuperscript{55,56} using essentially the same computational parameters as those used for the CRYSTAL14 calculations, but with a 400 eV cut-off for the plane wave basis set.\textsuperscript{57} The core electrons for each atom were described within the projector augmented plane wave (PAW) approach. The absorption coefficient ($\alpha$) of the materials was computed from the frequency dependent dielectric constant with the following formulae, where $\varepsilon_1$ and $\varepsilon_2$ are the real and imaginary terms of the dielectric constant, respectively:

\begin{equation}
\alpha(\omega) = \frac{4\pi k(\omega)}{\lambda}
\end{equation}

\begin{equation}
k(\omega) = \sqrt{\varepsilon_2^2 + \varepsilon_1^2 - \varepsilon_0^2}
\end{equation}

The methodology to compute all the electronic properties, including the bandgap (denoted $E_g$), dielectric constants, charge carrier effective masses ($m^*$) and exciton binding energies ($E_b$), is presented in the literature.\textsuperscript{58} Notably, the exciton binding energy is computed invoking the Wannier-Mott model that describes the exciton as a hydrogenic atom. This methodology was successfully applied to compute electronic properties of several families of semiconductors including hybrid perovskites,\textsuperscript{59} sulfides,\textsuperscript{60} oxysulfides,\textsuperscript{61} oxides\textsuperscript{51,62} and carbon nitrides.\textsuperscript{63,64} The HSE06 standard deviations are 10% and 3% for bandgaps and infinite dielectric constants respectively making HSE06 has one the most accurate functional for semiconductor properties.

3. Results and Discussion

3.1. Structural properties. SrTaO$_3$N thin films were synthesized using RF sputtering simultaneously on Nb:STO and MgO single crystal substrates with different thicknesses of 200, 400 and 900 nm (denoted as STON-200, STON-400 and STON-900, respectively). Both the Nb:STO and MgO substrates have a small crystallographic mismatch with the SrTaO$_3$N perovskite ($-3.94$ and $+3.59\%$, respectively), promoting a textured or epitaxial growth of the films. The crystal structures of the obtained films were characterized by XRD analysis with a 0-28 configuration, and the results are presented in Figure 1. All films have a crystalline structure corresponding to the SrTaO$_3$N phase characterized by the presence of the most prominent peaks with no impurity phases present.\textsuperscript{65} We can index the peaks according to a pseudo-cubic cell, deduced from the standard (orthorhombic) cell of SrTaO$_3$N as $c = \sqrt[3]{2}a$. We note for STON-200 that the indexed intense peaks correspond to the (00l) family of planes, indicating a preferred orientation of the layer along the c-axis of the oxynitride compound. [001] scans have been performed to investigate the alignment of the film axis to those of substrate in order to check a possible epitaxy of the STON-200 sample. Diffractionogramm given in Figure S1 indicates four peaks spaced by 90° for the film, aligned with the substrate, thus demonstrating the cube on cube growth of this oxynitride film on the NbSrTiO$_3$ substrate. However, considering the presence of the (100) peak in addition to the (00l) main contribution in Figure 1, the growth of STON-200 film can be only considered as textured. STON-400 and STON-900 with higher thickness show transitions to a more polycrystalline character, coincidentally losing the (00l) peak intensities. Ratios $c/a$ of samples were calculated, with $c$, the out-of-plane axis parameter, and $a$, the in-plane axis parameter. Ratios are in the range 1.002-1.005, which is close to the bulk value ($c/a = 1.002$)$^{55}$, meaning that the films investigated in the present study are relaxed, including the STON-200 textured film.

The chemical composition of samples was determined by semi-quantitative EDS and the results are compiled in Table S1. Although the EDS is known to be inaccurate for light element quantification such as oxygen and nitrogen, we can notice that the atomic percentages remain unchanged among the films with
different thickness. The Sr/Ta ratio is around 1.08 for all the films, indicating that the films are close to ideal stoichiometry and they have similar chemical compositions. The difference in optoelectronic properties among the samples, if any, does not originate from non-stoichiometry. Angular deviations from the tabulated values should not come from the reduced Ta states or anion vacancies (providing metallic character) but other factors, such as substrate strain.

Figure 1. XRD θ-2θ diffractogram patterns of different thickness of SrTaO$_3$N films deposited on (001) Nb:SSTO substrate (indexation of films is made according to a pseudo-cubic cell) (* represents the (001) diffraction peaks according to the substrate).

One of the main difficulties in the modeling of oxynitride perovskites is the description of the anion O/N ordering. Such anion ordering has been the subject of several publications both experimental and theoretical$^{44,47,63}$ and is put forward to explain the very high measured dielectric constants. Literature highlighted a local anion organization in SrTaO$_3$N. More precisely, there are two N atoms and four O atoms surrounding the Ta atoms, with a pseudo-octahedral structure. Clark et al. proved that the most stable organization of the anions around the Ta atoms is a cis configuration for the two N atoms.$^{26}$

Studies of SrTaO$_3$N have emphasized that the perovskite electronic properties can be influenced by the anionic ordering as well. There are two possibilities for the O$^{2-}$ and N$^-$ ion positions around the cation: two nitrogen ions can occupy either adjacent (cis-type) or opposite (trans-type) sites in a BO$_2$N$_2$ octahedral structure. Neutron powder diffraction data, refined in the tetragonal $I4/mcm$ system, show two anion sites with different O/N occupancies.$^{44}$ That way, the O/N ratio is 50/50 on the axial sites (4a) and 75/25 on the equatorial site (8h). Assuming so, a cis-type configuration, the possibility of well-ordered local anion organizations has been both theoretically and experimentally demonstrated.$^{55,67}$ The influence of this local ordering is major field of investigation and some preliminary studies on GaTaO$_3$N indicate an influence of the anions on the bandgap and band positions.$^{15}$ But, its influence on for SrTaO$_3$N compound and on dielectric constants has not been investigated to date. For that reason, in this work, several properties were computed on various anion orderings. SrTaO$_3$N was
modeled starting with the unit cell proposed by Kim et al. having the space group P4/mcm based on a formula units, and the geometries were optimized. Considering this structure, all possible anion orderings were investigated with the only constraint that the N atoms are placed in a cis conformation around the Ta atoms. This configuration is consistent with the fact that our films are not strained, as demonstrated by XRD analysis. During the geometry optimization, all degrees of freedom were allowed to change. The final geometries and their relative energies are presented in Figure 2. In this figure, the structures noted S2, S4 and S5 correspond, respectively, to the 90°, 0° and 180° denotation given by Hinuma et al. where the angle corresponds to the dihedral angle of consecutive N-Ta-N-Ta-N atoms.

The measured and optimized cell parameters are given in Table S2 along with the atomic coordinates for all the structures (Tables S3-S8). The difference between the computed and experimental cell parameters remains in the expected range of error for the PBE0 functional (around 1.2%). The relative energy between the most stable and less stable structures is only 36 meV/formula units corresponding to 3.5 kJ mol$^{-1}$ of SrTaO$_2$N. Knowing that the synthesis was performed at high temperature (900°C), all the investigated structures can be observed experimentally in the material. The configuration S1, with full nitrogen occupancy in the equatorial sites, is in agreement with the most stable (cis) structures presented by Oka et al. Moreover, as in the study of Hinuma et al., S2 (which corresponds to their ‘90-deg’ model) is the most stable structure among those with axial 50/50 and equatorial 75/25 O/N occupancies.

3.2. Optical properties. The transmittance spectra of the films deposited on MgO substrates are shown in Figure S2A. Additionally, typical fringes resulting from interferences between the air/film and film/substrate interfaces are observed. Their oscillation amplitude and width depend on the thickness and the refractive index of the film. These oscillations increase with film thickness assuming that the films are composed of the same phase. The films reflectance was also measured and the results are presented in Figure S2B. From both transmittance and reflectance contributions with an accurate account of the films thicknesses, we can reasonably access the absorption coefficient of the material using the following equation: 

$$\alpha = \frac{1}{t} \ln \left( \frac{T}{(1-R)^2} \right)$$

where $\alpha$ is the absorption coefficient, $t$ is the film thickness, $T$ is the transmittance, and $R$ is the reflectance.

As shown in Figure 3A, STON-200 textured film exhibited absorption coefficients of up to $4 \times 10^3$ cm$^{-1}$ in the 300 – 550 nm spectral range that is similar or relatively higher than Si and GaAs used for photovoltaic devices. Estimated absorption edges are observed in the range [520-570 nm] for the films, which is consistent with that reported for SrTaO$_2$N materials. STON-400 and STON-900 exhibit a similar behavior with lower absorptions and a shift of the edge to approximately 500 nm (at $2 \times 10^3$ cm$^{-1}$). Figure S3 shows the Tauc plots of the SrTaO$_2$N films. The evolution of the absorption edge is in coherence with the variation of the bandgap observed for the films where STON-200 has the smallest bandgap (2.4 eV) and STON-900 the highest (2.6 eV). It is worth noting that the change in crystal structure from textured to polycrystalline growth is concomitant with the shift in the absorption edge in the SrTaO$_2$N films. These evolutions may be, at least partially, explained by an anion ordering. It is worth mentioning that determination of bandgap for the powder semiconductor using Kubelka-Munk function (e.g., 2.1 eV) often leads to underestimation of bandgap values, partly exaggerating the contribution of defect states. Reported bandgaps for SrTaO$_2$N thin films were 2.3-2.5 eV, consistent with the values reported in this study. We emphasize that, for solar energy conversion system, determination of absorption coefficient provides more valuable information than bandgap determination only, because it provides precise thickness required to absorb sufficient photons (thus achievable efficiencies) as a function of wavelengths.

![Figure 3](image-url)
3.3. Dielectric and transport properties. In solar conversion devices, it is important to examine the charge carrier separation inside the semiconductor. The extraction of charge is greatly influenced by the material’s dielectric constant. In general, a high dielectric constant is known to induce efficient charge separation of carriers. The dielectric constant links the polarization ($\mathbf{D}$) of a dielectric material to the external electric field ($\mathbf{E}$) applied on it (6).

$$\mathbf{D} = \varepsilon_0 \varepsilon_r \mathbf{E}$$

(6)

This dielectric constant represents the ability of a dielectric material to screen the external electric field by the apparition of a polarization. This phenomenon originates from the reorganization of the electronic density and/or from the motion of the ions constituting the material. The contribution of the dielectric constant induced by the electronic density is noted $\varepsilon_e$ (generally called infinite dielectric constant) and the contribution involving the ionic motions is named $\varepsilon_\text{dip}$. Finally we have:

$$\varepsilon_r = \varepsilon_e + \varepsilon_\text{dip}$$

(7)

At high frequencies ($10^{14}$-to-$10^{15}$ Hz), the dielectric constant experimentally determined via spectroscopy contains only the electronic contribution. At lower frequencies ($<$ $10^4$ Hz), the dielectric constant includes the electronic and the vibrational contributions, but the latter dominates.

To estimate the electronic dielectric constant, we use the complex index of refraction $N = n + ik$. We calculate the electronic dielectric constant from the real part of
the refractive index from the reflectance and transmittance measurements, using the following relations:

$$n = \frac{1 + R}{1 - R} + \sqrt{\frac{4R}{(1 - R)^2 - k^2}} \tag{8}$$

Then, the real term of the dielectric constant is $\epsilon_r = n^2 - k^2$ and the imaginary term (dielectric loss) is $\epsilon_i = 2nk$. At low frequency, the dielectric constant of the material can be deduced from the measurement of the capacitance of a metal insulator metal (MIM) structure.

Figure 5A displays the evolution of the electronic contribution to the dielectric constant as a function of the photon energy. For all samples, $\epsilon_{\text{ee}}$ was measured between 5 and 6. The electronic dielectric constant seems insensitive to the film thickness and crystallization. The computed $\epsilon_{\text{ee}}$ was around 5.6-5.8 whatever the structure and falls in the range of measured ones confirming once more both the accuracy of HSE06 functional and the model used to simulate the anion ordering. The low value of the electronic contribution to the dielectric constant obtained theoretically confirms strong ionicity of the material leading to a weakly polarizability electron density. The static dielectric constant $\epsilon_0$ was measured to be approximately 80 in a large frequency range [1-100 kHz] (Figure 5B). This value is in accordance with previously reported studies, but lower than the one measured on epitaxial trans-type SrTaO$_3$N ($\epsilon_r = 2000 @10$ kHz) films deposited by nitrogen-enhanced laser ablation. In the previous reports regarding ferroelectricity of this compound, a cis-type ordering induces a local polarity, and a TaO$_4$N$_6$ octahedron tilting which may explain the high $\epsilon_r$.

Recently, Kikkawa and coworkers have highlighted the significance of a relaxor behavior in bulk SrTaO$_3$N, which accounts for local ferroelectric behavior. On the other hand, Oka et al. reported a tetragonal distortion that could lead to a trans-type configuration on very thin SrTaO$_3$N film with a compressive strain due to the mismatch between the substrate and the oxy nitride cell. That specific O/N order could explain the ferroelectric behaviour, observed by piezoresponse force microscopy.

Moreover, one key finding of our study is that this particular value remains very high whatever the anionic organization considered. The computed static dielectric constants ($\epsilon_r$) including both electronic ($\epsilon_{\text{ee}}$) and vibrational contributions ($\epsilon_{\text{vv}}$) are in the range 53-65, in agreement with the measured values in this study and values found in the literature. The relatively larger discrepancy between theory and experiment was found for the vibrational dielectric constant ($\epsilon_{\text{vv}}$) compared to the electronic one ($\epsilon_{\text{ee}}$). The description of the anharmonic soft vibrational modes leads to a noticeable error when computing their frequencies in the harmonic approximation. Another source of error may come from long-range anion ordering leading to vibrational modes delocalized on a large scale, which is not necessarily taken into account with the unit cell size used in this modeling. Nevertheless, the general agreement between theory and experiment obtained in this study confirms that our unit cell sizes and anion orderings could capture the main physical phenomena. In the framework of our model and calculations, anion ordering has little influence on the SrTaO$_3$N dielectric properties, consistent with the conclusions given by Withers et al. for the BaTaO$_3$N material. They assumed the presence of inherently polar, off-center and oppositely directed displacements of Ta and neighboring O/N ions which would give rise to one-dimensional polar nano-regions responsible for the high dielectric constant of BaTaO$_3$N. They suggest that the role of the anionic ordering is to set up random local strain fields suppressing transverse correlations of the inherent <001> chain dipoles and inhibiting the development of a long range ordered ferroelectric state.

Figure 5. (A) The electronic contribution to the dielectric properties of the SrTaO$_3$N films measured using UV-visible transmittance and reflectance spectra. (B) The vibrational contribution to the dielectric properties of the STON-400 film measured using a metal-insulating-metal (MIM) structure.

Our calculations also include the computation of the effective masses of electrons and holes that is directly to the electron and hole mobility of the material. In this discussion, we will use the approximation that the
charge mobilities are only dependent of the effective masses. Table 1 lists the impact of anion ordering on the effective masses of electrons and holes. The calculated values are in the range of 0.3-0.8 for electrons and 0.4-4.8 for holes highlighting the large sensitivity of the holes on the anion ordering. From chemical intuition point of view, this is the expected behaviour since the holes are localized on the valence band, so on the anions, and the electrons on the Ta atoms, so less sensitive on the anions. These results are in reasonable agreement with calculations performed on some perovskite structures including SrTaO₃N (0.5 for electrons).

Heavy holes may be the reason behind the reported inefficacy of ATaO₃N oxynitrides to oxidize water in the powder suspension photocatalysis (A: Sr, Ca, Ba). The charge carrier mobility is expected to be high for electrons (i.e. majority carrier with an effective mass less than 0.5mₑ); but relatively low for the minority carrier in n-type SrTaO₃N. By combining the effective masses and the dielectric constants, the exciton binding energies were calculated. Very low values between 0.8 and 1.3 meV were obtained, mainly as a result of the large dielectric constant. Keeping in mind that the room temperature thermal energy is around 25 meV, this indicates that the material can efficiently dissociate the photo-generated excitons leading to generation of free charge carriers.

Table 1. Computed effective masses of electrons and holes calculated for the different SrTaO₃N geometries as defined in the main text (HSE06), in three different crystallographic directions. AVE and STD. DEV mean average and standard deviation, respectively.

<table>
<thead>
<tr>
<th>Effective mass</th>
<th>[100]</th>
<th>[101]</th>
<th>[111]</th>
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<tbody>
<tr>
<td>Hole (m*ₜ/mₑ)</td>
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<tr>
<td>S₁</td>
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<td>2.4</td>
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</tr>
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<td>0.4</td>
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<td>0.7</td>
</tr>
<tr>
<td>AVE.</td>
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<td>1.5</td>
</tr>
<tr>
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</tr>
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<td>0.5</td>
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</tr>
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<tr>
<td>S₃</td>
<td>0.8</td>
<td>0.6</td>
<td>0.6</td>
</tr>
<tr>
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<td>0.8</td>
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<td>0.4</td>
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<tr>
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</tr>
<tr>
<td>S₆</td>
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<tr>
<td>AVE.</td>
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3.4. Band positions. To complete our characterization of the SrTaO₃N material with the aim of using this material as a photoelectrode or photocatalyst, Mott-Schottky measurements were carried out on the STON-200 film deposited on the Nb:STO substrate because this sample showed the excellent textured crystalline growth along with a high absorption coefficient. A frequency range of 631 Hz to 1 kHz was chosen based on the Bode plot (Figure S4), and the potential range (0.1-1.3 V vs. RHE) was chosen to be the double-layer region in which there were no Faradic currents (Figure S5). Figure 6A shows the Mott-Schottky plot for the STON-200 film. The observed positive slope is indicative of an n-type characteristic. The flatband potential was deduced from the intercept of the plot as a function of the applied potential E, yielding a value of -0.2 V vs. RHE in excellent agreement with what was recently reported on the SrTaO₃N-based electrode fabricated from its powder form. The majority carrier concentration (Nᵥ) was estimated to be as large as 3 x 10¹⁸ cm⁻³ from the slope of the plot with the measured dielectric constant of 80.

Figure 6. (A) Mott-Schottky measurements of the STON-200 thin film on Nb:STO (in Ar, 0.1 M Na₂SO₄, pH 8.8). (B) A schematic diagram of the band edge positions of the SrTaO₃N structure.

A schematic illustration of the estimated band edge positions are shown in Figure 6B in the RHE scale. SrTaO₃N a conduction band edge more negative than the hydrogen evolution potential (AE = 200 mV) and the valence band edge well below the standard potential for water oxidation (AE = 2970 mV). It was previously suggested that the valence band potential may not be located to provide sufficient overpotential for water oxidation; nevertheless, our Mott-Schottky
analysis showed favorable band edge positions for overall water splitting, substantially straddling water redox potentials (Figure 6B). An effective charge separation strategy is required to efficiently extract and generate sufficient oxidation equivalents in the appropriate electrocatalyst for splitting water. Moreover, protection against self-induced photocorrosion in the aqueous environment may alleviate to some degree such hole transport limitations.

Table 2 summarizes all the properties measured and computed for SrTaO$_3$N in this work. The properties for each computed structure (Si-S6) are compiled in Table S9. Besides the good experiment vs. theory agreement, this table reflects that the unit cells and anion orderings selected for the DFT investigation were large enough to capture the electronic properties of the system. The bandgap was affected only slightly by the anion ordering while the electronic dielectric constant was almost unchanged by this structural feature. On the other hand, the vibrational contribution was much more affected by anion ordering and a better simulation of this property could be obtain with larger unit cells and more anion organizations with the limitation that the soft modes contributing to this property are anharmonic thus difficult to model with high accuracy. Because the conduction band is constituted by Ta orbitals, electron effective masses is weakly affected by anion ordering in the opposite to hole effective masses computed on the valence band made of N orbitals.

<table>
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<td>5.6-5.8</td>
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<tr>
<td>$m^*_h / m_e$</td>
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<tr>
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<tr>
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<td></td>
</tr>
<tr>
<td>$E_{cb}$ / V vs. RHE</td>
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4. Conclusions
A combined experimental and theoretical approach was implemented to understand the photophysical properties of SrTaO$_3$N, including the absorption coefficient, dielectric constant and effective mass. The textured, well crystalline structure thin film was synthesized by RF sputtering to be able to extract intrinsic optical and electrical properties. State of the art DFT calculations were performed involving the range separated hybrid functional HSE06 leading to an excellent agreement between measured and experimental properties and offering an atomistic interpretation of the properties of SrTaO$_3$N. Both the measurements and the calculations showed high optical absorption in the visible range with a high dielectric constant. The optical properties (bandgap and absorption coefficient) are the main parameters affected by the anion ordering in the SrTaO$_3$N perovskite structure. No paramount effect of the anion ordering was observed on the dielectric properties. We predict high mobility for the majority carriers (~0.5 m$_e$); however, care must be taken to account for probable heavy holes. In terms of band alignment, SrTaO$_3$N straddles the water redox potentials, which means that the material has potential for visible-light driven overall water splitting. The thin film photophysical experimental characterizations and theoretical calculations presented in this study are excellent tools for the understanding and the development of the photoconversion efficiency.

ASSOCIATED CONTENT
Supporting Information. Figure S1. X-ray diffraction $\phi$-scans at $\chi = 45^\circ$ of the STON-300 film and Nb:STO substrate associated with the (10) plane of the pseudo-cubic cells; Figure S2. Transmittance (A) and reflectance (B) spectra of the measured SrTaO$_3$N films; Figure S3. Tauc plots for direct allowed transition of the SrTaO$_3$N films; Figure S4. Bode (A) and Nyquist impedance spectra (B) of the measured STON-300 film; Figure S5. CV measurements of the measured STON-300 film with different scan rates; Table S1. Chemical composition estimated by EDS data; Table S2. Experimental and computed cell parameters for different anion ordering in the I4/mcm space group; Table S3 to S8 Geometry of structure (Si) to (S6); Table S9. Computed properties for structure (Si) to (S6). This material is available free of charge via the Internet at http://pubs.acs.org.*

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REFERENCES


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